## FORM PTO-1449 (Modified) LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT(S)' INFORMATION DISCLOSURE STATEMENT APPLICANT: Lidu Huang, et al. FILING DATE: March 24, 2004 REFERENCE DESIGNATION U.S. PATENT DOCUMENTS POCLIMENT DATE NAME Class Subclass Filing Date

REFERENCE DESIGNATION		U.S. P	ATENT DOCUMENTS				
EXAMPR INITIAL		DOCUMENT NUMBER	DATE	NAME	Class	Subclass	Filing Date : If Appropriate
KG	A1	6,504,966	01/07/2003	Kato et al.	385	16	
	A2						
	A3						
	A4						

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OTHER ART (Include Author, Title, Date, Pertinent Pages, Etc.) C1 "Silica Integrated Optical Circuits", edited by H. M. Presby, Section 2 "Fabrication", SPIE KG Milestone Series, vol. MS 125, pp. 43-149, 1996 C2 T. Fukano and I. Yamoguchi, "Simultaneous measurement of thickness and refractive indices of multilayers by a low-coherence confocal interference microscope", Opt. Lett., vol. 21, pp. KG 1942-1944, 1996 C3 G. J. Veldhuis, L.E. W. van Veen and P. V. Lambeck, "Integrated optical refractometer based KG on waveguide bend loss", IEEE J. Lightwave Technol., vl. 17, pp. 857-864, 1999 D. C. Yin and Y. Inatomi, "Measurement of refractive index of GaP crystal over a large C4 KG temperature range using interferometry", Cryst. Res. Technol., vol. 35, pp. 221-228, 2000 T. Dennis, E. M. Gill and S. L. Gilbert, "Interferometric measurement of refractive-index C5 KG change in photosensitive glass", Appl. Optics, vol. 40, pp. 1663-1667, 2001 C6 O. M. Efimov, L. B. Glebov and H. P. Andre, "Measurement of the induced refractive index in a photothermorefractive glass by a liquid-cell shearing interferometer", Appl. Optics, vol. 41, KG pp.1864-1870, 2002

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	/Kara Geisel/ (12/26/2006)		

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